Maskless Lithography and Multibeam Mask Writer Workshop
May 10, 2010
Agenda

8:30 AM – 9:00 AM	**Continental Breakfast**	
9:00 AM – 9:10 AM	**Welcome**	***L. Litt, GLOBALFOUNDRIES/SEMATECH*** ***G. Hughes, SEMATECH***
9:10 AM – 9:30 AM	**ML2 Wafer Writer Overview**	***L. Litt, GLOBALFOUNDRIES/SEMATECH***
9:30 AM – 11:00 AM	**Supplier Presentations**	***B.J. Kampherbeek, MAPPER Lithography*** ***C. Bevis, KLA-Tencor*** ***A. Yamada, Advantest*** ***H. Smith, LumArray***
11:00 AM – 12:30 PM	**Customer User Perspective**	***J.H. Chen, TSMC*** ***L. Pain, CEA-Leti*** ***Y. Borodovsky, Intel****
12:30 PM – 1:30 PM	**Lunch**	
1:30 PM – 2:15 PM	**Breakout**	***L. Litt, GLOBALFOUNDRIES/SEMATECH*** ***G. Hughes, SEMATECH***
2:15 PM – 2:45 PM	**Mask Pattern Generator Overview**	***G. Hughes, SEMATECH***
2:45 PM – 3:45 PM	**Supplier Presentations**	***M. Slodowski, Vistec Electron Beam GmbH*** ***M. Yamabe, ASET*** ***H. Yasuda, PARAM***
3:45 PM – 4:45 PM	**Customer Perspective**	***N. Hayashi, Dai Nippon Printing*** ***F. Kalk, Toppan***
4:45 PM – 5:30 PM	**Breakout**	***G. Hughes, SEMATECH*** ***L. Litt, GLOBALFOUNDRIES/SEMATECH***
5:30 PM	**Summary and Conclusions**	***G. Hughes, SEMATECH*** ***L. Litt, GLOBALFOUNDRIES/SEMATECH***

***** ML2 and MBMW***